Shunri Oda

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#	Paper	IF	Citations
293	A quantum-dot spin qubit with coherence limited by charge noise and fidelity higher than 99.9. <i>Nature Nanotechnology</i> , 2018 , 13, 102-106	28.7	340
292	Photoluminescence mechanism in surface-oxidized silicon nanocrystals. <i>Physical Review B</i> , 1997 , 55, R73	3 7,5 -R7	37484
291	A fault-tolerant addressable spin qubit in a natural silicon quantum dot. <i>Science Advances</i> , 2016 , 2, e160	10.64934	120
290	A flexible and wearable terahertz scanner. <i>Nature Photonics</i> , 2016 , 10, 809-813	33.9	106
289	Electron trapping, storing, and emission in nanocrystalline Si dots by capacitanceNoltage and conductanceNoltage measurements. <i>Journal of Applied Physics</i> , 2003 , 93, 576-581	2.5	101
288	Fabrication of Nanocrystalline Silicon with Small Spread of Particle Size by Pulsed Gas Plasma. <i>Japanese Journal of Applied Physics</i> , 1997 , 36, 4031-4034	1.4	100
287	Nanocrystalline silicon electron emitter with a high efficiency enhanced by a planarization technique. <i>Journal of Applied Physics</i> , 2002 , 92, 2748-2757	2.5	89
286	Highly Oriented ZnO Films Prepared by MOCVD from Diethylzinc and Alcohols. <i>Japanese Journal of Applied Physics</i> , 1985 , 24, 1607-1610	1.4	78
285	Diagnostic Study of VHF Plasma and Deposition of Hydrogenated Amorphous Silicon Films. <i>Japanese Journal of Applied Physics</i> , 1990 , 29, 1889-1895	1.4	71
284	ZnS blue-light-emitting diodes with an external quantum efficiency of 5🛮 0 🗗 . <i>Applied Physics Letters</i> , 1975 , 27, 697-699	3.4	71
283	Preparation of Polycrystalline Silicon by Hydrogen-Radical-Enhanced Chemical Vapor Deposition. Japanese Journal of Applied Physics, 1987 , 26, L10-L13	1.4	70
282	Electron Transport in Nanocrystalline Si Based Single Electron Transistors. <i>Japanese Journal of Applied Physics</i> , 2000 , 39, 4647-4650	1.4	69
281	Charge injection and trapping in silicon nanocrystals. <i>Applied Physics Letters</i> , 2005 , 87, 182101	3.4	60
280	Emission lifetime of polarizable charge stored in nano-crystalline Si based single-electron memory. Journal of Applied Physics, 2001 , 90, 6402-6408	2.5	57
279	Growth of Amorphous and Crystalline Silicon by HR-CVD (Hydrogen Radical Enhanced CVD). <i>Materials Research Society Symposia Proceedings</i> , 1987 , 95, 225		56
278	Quantum confinement energy in nanocrystalline silicon dots from high-frequency conductance measurement. <i>Journal of Applied Physics</i> , 2003 , 94, 7261-7265	2.5	54
277	A new emission band in self-activated ZnS. <i>Journal of Luminescence</i> , 1979 , 18-19, 829-832	3.8	45

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276	Hopping conduction in size-controlled Si nanocrystals. <i>Journal of Applied Physics</i> , 2006 , 100, 014303	2.5	42
275	Frequency effects in processing plasmas of the VHF band. <i>Plasma Sources Science and Technology</i> , 1993 , 2, 26-29	3.5	42
274	Fabrication and Electrical Characteristics of Single Electron Tunneling Devices Based on Si Quantum Dots Prepared by Plasma Processing. <i>Japanese Journal of Applied Physics</i> , 1997 , 36, 4038-4041	1.4	41
273	Preparation of Microcrystalline Silicon Films by Very-High-Frequency Digital Chemical Vapor Deposition. <i>Japanese Journal of Applied Physics</i> , 1992 , 31, 1948-1952	1.4	41
272	Magnetic field dependence of Pauli spin blockade: A window into the sources of spin relaxation in silicon quantum dots. <i>Physical Review B</i> , 2012 , 86,	3.3	40
271	Study of structural and optical properties of nanocrystalline silicon embedded in SiO2. <i>Thin Solid Films</i> , 2000 , 375, 137-141	2.2	40
270	Selective Etching of Hydrogenated Amorphous Silicon by Hydrogen Plasma. <i>Japanese Journal of Applied Physics</i> , 1994 , 33, 4442-4445	1.4	39
269	Probing electron charging in nanocrystalline Si dots using Kelvin probe force microscopy. <i>Applied Physics Letters</i> , 2004 , 85, 3262-3264	3.4	34
268	Evidence of storing and erasing of electrons in a nanocrystalline-Si based memory device at 77 K. Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena, 2002 , 20, 1135		34
267	The Role of Hydrogen Radicals in the Growth of a-Si and Related Alloys. <i>Japanese Journal of Applied Physics</i> , 1986 , 25, L188-L190	1.4	34
266	Preparation of a-Si:H Films by VHF Plasma CVD. <i>Materials Research Society Symposia Proceedings</i> , 1988 , 118, 117		34
265	Nanocrystalline silicon formation in a SiH4 plasma cell. <i>Journal of Non-Crystalline Solids</i> , 1996 , 198-200, 875-878	3.9	33
264	Charge storage in nitrided nanocrystalline silicon dots. <i>Applied Physics Letters</i> , 2005 , 87, 173107	3.4	32
263	Electron transport in a single silicon quantum structure using a vertical silicon probe. <i>Journal of Applied Physics</i> , 2000 , 88, 4186	2.5	32
262	NeoSilicon materials and silicon nanodevices. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2003 , 101, 19-23	3.1	31
261	Enhanced Dielectric Properties in SrTiO3/BaTiO3Strained Superlattice Structures Prepared by Atomic-Layer Metalorganic Chemical Vapor Deposition. <i>Japanese Journal of Applied Physics</i> , 1999 , 38, 6817-6820	1.4	31
260	Tip-enhanced Raman mapping of a single Ge nanowire. <i>Applied Physics Letters</i> , 2011 , 99, 053112	3.4	30
259	Nanoelectromechanical nonvolatile memory device incorporating nanocrystalline Si dots. <i>Journal of Applied Physics</i> , 2006 , 100, 094306	2.5	29

258	Toward long-term retention-time single-electron-memory devices based on nitrided nanocrystalline silicon dots. <i>IEEE Nanotechnology Magazine</i> , 2004 , 3, 210-214	2.6	29
257	Properties of a-Si based alloys prepared from fluorides and hydrogen. <i>Journal of Non-Crystalline Solids</i> , 1985 , 77-78, 877-880	3.9	29
256	Observation of the single electron charging effect in nanocrystalline silicon at room temperature using atomic force microscopy. <i>Applied Physics Letters</i> , 1998 , 72, 1089-1091	3.4	27
255	Preparation of Nanocrystalline Silicon by Pulsed Plasma Processing. <i>Materials Research Society Symposia Proceedings</i> , 1994 , 358, 721		27
254	Epitaxial Growth of YBaCuO Films on Sapphire at 500°C by Metalorganie Chemical Vapor Deposition. <i>Japanese Journal of Applied Physics</i> , 1989 , 28, L427-L429	1.4	27
253	Properties of Metalorganic Precursors for Chemical Vapor Deposition of Oxide Superconductors. Japanese Journal of Applied Physics, 1990 , 29, L1072-L1074	1.4	27
252	Hydrogen radical assisted chemical vapor deposition of ZnSe. <i>Applied Physics Letters</i> , 1986 , 48, 33-35	3.4	27
251	Room temperature single electron charging in single silicon nanochains. <i>Journal of Applied Physics</i> , 2008 , 103, 053705	2.5	26
250	Thermal-aware device design of nanoscale bulk/SOI FinFETs: Suppression of operation temperature and its variability 2011 ,		25
249	Influence of nanocrystal size on the transport properties of Si nanocrystals. <i>Journal of Applied Physics</i> , 2008 , 104, 024518	2.5	25
248	Construction of amorphous silicon ISFET. Sensors and Actuators, 1989, 16, 55-65		25
247	Utilizing self-assembled-monolayer-based gate dielectrics to fabricate molybdenum disulfide field-effect transistors. <i>Applied Physics Letters</i> , 2016 , 108, 041605	3.4	24
246	Single-Electron Tunneling Devices Based on Silicon Quantum Dots Fabricated by Plasma Process. Japanese Journal of Applied Physics, 2000 , 39, 264-267	1.4	24
245	Carrier conduction in a Si-nanocrystal-based single-electron transistor-I. Effect of gate bias. <i>Superlattices and Microstructures</i> , 2000 , 28, 177-187	2.8	23
244	Single Electron Memory Devices Based on Plasma-Derived Silicon Nanocrystals. <i>Japanese Journal of Applied Physics</i> , 2000 , 39, L855-L857	1.4	23
243	Visible Electroluminescence from Spherical-Shaped Silicon Nanocrystals. <i>Japanese Journal of Applied Physics</i> , 2008 , 47, 8137-8140	1.4	22
242	Preparation and characterization of low-resistivity ZnS for blue LEDQ. <i>IEEE Transactions on Electron Devices</i> , 1977 , 24, 956-958	2.9	22
241	Characterization and suppression of low-frequency noise in Si/SiGe quantum point contacts and quantum dots. <i>Applied Physics Letters</i> , 2013 , 102, 123113	3.4	21

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240	Room Temperature Single-Electron Narrow-Channel Memory with Silicon Nanodots Embedded in SiO2 Matrix. <i>Japanese Journal of Applied Physics</i> , 2000 , 39, L792-L795	1.4	21	
239	The role of hydrogen radicals in nucleation and growth of nanocrystalline silicon. <i>Journal of Non-Crystalline Solids</i> , 1993 , 164-166, 993-996	3.9	21	
238	Experimental study of self-heating effect (SHE) in SOI MOSFETs: Accurate understanding of temperatures during AC conductance measurement, proposals of 20method and modified pulsed IV 2012 ,		20	
237	Conducting-tip atomic force microscopy for injection and probing of localized charges in silicon nanocrystals. <i>Applied Physics Letters</i> , 2003 , 83, 3788-3790	3.4	20	
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234	In SituMonitoring of Optical Reflectance Oscillation in Layer-by-Layer Chemical Vapor Deposition of Oxide Superconductor Films. <i>Japanese Journal of Applied Physics</i> , 1992 , 31, L1243-L1245	1.4	19	
233	High quality a-Si:H films and interfaces prepared by VHF plasma CVD. <i>Journal of Non-Crystalline Solids</i> , 1991 , 137-138, 677-680	3.9	19	
232	Lithographically defined few-electron silicon quantum dots based on a silicon-on-insulator substrate. <i>Applied Physics Letters</i> , 2015 , 106, 083111	3.4	18	
231	An electronic synaptic device based on HfOTiO bilayer structure memristor with self-compliance and deep-RESET characteristics. <i>Nanotechnology</i> , 2018 , 29, 415205	3.4	18	
230	3-D Design and Analysis of Functional NEMS-gate MOSFETs and SETs. <i>IEEE Nanotechnology Magazine</i> , 2007 , 6, 218-224	2.6	18	
229	Electric Properties of Coplanar High-TCSuperconducting Field-Effect Devices. <i>Japanese Journal of Applied Physics</i> , 1998 , 37, 492-495	1.4	18	
228	Role of Hydrogen Radical Treatment in Nucleation of Nanocrystalline Silicon. <i>Japanese Journal of Applied Physics</i> , 1992 , 31, L1443-L1445	1.4	18	
227	Electrophotographic studies of glow-discharge amorphous silicon. <i>The Philosophical Magazine: Physics of Condensed Matter B, Statistical Mechanics, Electronic, Optical and Magnetic Properties</i> , 1981 , 43, 1079-1089		18	
226	Control of Electrostatic Coupling Observed for Silicon Double Quantum Dot Structures. <i>Japanese Journal of Applied Physics</i> , 2008 , 47, 4820-4826	1.4	17	
225	Integration of Tunnel-Coupled Double Nanocrystalline Silicon Quantum Dots with a Multiple-Gate Single-Electron Transistor. <i>Japanese Journal of Applied Physics</i> , 2007 , 46, 4386-4389	1.4	17	
224	Preparation of YBa2Cu3OxThin Films by Layer-by-Layer Metalorganic Chemical Vapor Deposition. <i>Japanese Journal of Applied Physics</i> , 1992 , 31, L787-L789	1.4	17	
223	Preparation of Highly Photoconductive a-SiGexfrom Fluorides by Controlling Reactions with Atomic Hydrogen. <i>Japanese Journal of Applied Physics</i> , 1986 , 25, L540-L543	1.4	17	

222	Formation Mechanism of 100-nm-Scale Periodic Structures in Silicon Using Magnetic-Field-Assisted Anodization. <i>Japanese Journal of Applied Physics</i> , 2008 , 47, 7398-7402	1.4	16
221	VaporliquidBolid Growth of Small- and Uniform-Diameter Silicon Nanowires at Low Temperature from Si2H6. <i>Applied Physics Express</i> , 2008 , 1, 014003	2.4	16
220	Silicon-on-insulator-based radio frequency single-electron transistors operating at temperatures above 4.2 K. <i>Nano Letters</i> , 2008 , 8, 4648-52	11.5	16
219	Two-Gate Transistor for the Study of Si/SiO2Interface in Silicon-on-Insulator Nano-Channel and Nanocrystalline Si Memory Device. <i>Japanese Journal of Applied Physics</i> , 2000 , 39, 4637-4641	1.4	16
218	Silicon-based single-electron memory using a multiple-tunnel junction fabricated by electron-beam direct writing. <i>Applied Physics Letters</i> , 1999 , 75, 1422-1424	3.4	16
217	Preparation of Nanocrystalline Silicon Quantum Dots by Pulsed Plasma Processes with High Deposition Rates. <i>Materials Research Society Symposia Proceedings</i> , 1999 , 571, 43		16
216	Preparation of nanocrystalline silicon quantum dot structure by a digital plasma process. <i>Advances in Colloid and Interface Science</i> , 1997 , 71-72, 31-47	14.3	15
215	Atomic Layer-by-Layer MOCVD of Complex Metal Oxides and In Situ Process Monitoring. <i>Chemical Vapor Deposition</i> , 2001 , 7, 7-18		15
214	Ballistic transport in silicon vertical transistors. <i>Journal of Applied Physics</i> , 2002 , 92, 1399-1405	2.5	15
213	Conductance quantization in nanoscale vertical structure silicon field-effect transistors with a wrap gate. <i>Applied Physics Letters</i> , 2000 , 76, 2922-2924	3.4	15
212	Atomic layer controlled metalorganic chemical vapor deposition of superconducting YBa2Cu3Ox films. <i>Journal of Crystal Growth</i> , 1994 , 145, 232-236	1.6	15
211	Electronic States In Glow-Discharge a-SiGex:H:(F) Alloys. <i>Japanese Journal of Applied Physics</i> , 1986 , 25, 49-52	1.4	15
210	High-density assembly of nanocrystalline silicon quantum dots. Current Applied Physics, 2006, 6, 344-347	' 2.6	14
209	Self-aligned double-gate single-electron transistor derived from 0.12-th-scale electron-beam lithography. <i>Applied Physics Letters</i> , 2001 , 78, 2070-2072	3.4	14
208	Electrical Properties of SrTiO[sub 3]/BaTiO[sub 3] Strained Superlattice Films Prepared by Atomic Layer Metallorganic Chemical Vapor Deposition. <i>Journal of the Electrochemical Society</i> , 2000 , 147, 4615	3.9	14
207	Preparation and Characterization of YBaCuO Superconducting Films by Low-Temperature Chemical Vapor Deposition Using Diketonate Complex and N2O. <i>Japanese Journal of Applied Physics</i> , 1992 , 31, 3839-3843	1.4	14
206	Design of multiple layered a-Si:H(F)/a-SiGex:H(F) films for enhancement in photoresponse in the near-infrared spectrum. <i>Applied Physics A: Solids and Surfaces</i> , 1986 , 41, 259-265		14
205	Preparation Method and Optoelectrical Properties of a-Se/CdxSe1-xMultilayer Films. <i>Japanese Journal of Applied Physics</i> , 1987 , 26, 991-995	1.4	14

204	Hole Transport in Silicon Thin Films with Variable Hydrogen Content. <i>Japanese Journal of Applied Physics</i> , 1987 , 26, L276-L279	1.4	14	
203	Characteristics of multilevel storage and switching dynamics in resistive switching cell of Al2O3/HfO2/Al2O3 sandwich structure. <i>Journal Physics D: Applied Physics</i> , 2018 , 51, 025102	3	14	
202	Quantum dots in single electron transistors with ultrathin silicon-on-insulator structures. <i>Applied Physics Letters</i> , 2015 , 107, 013102	3.4	13	
201	Dual Function of Single Electron Transistor Coupled with Double Quantum Dot: Gating and Charge Sensing. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 04CJ01	1.4	13	
200	Self-Heating Effects and Analog Performance Optimization of Fin-Type Field-Effect Transistors. Japanese Journal of Applied Physics, 2013 , 52, 04CC03	1.4	13	
199	Three-Dimensional Numerical Analysis of Switching Properties of High-Speed and Nonvolatile Nanoelectromechanical Memory. <i>IEEE Transactions on Electron Devices</i> , 2007 , 54, 1132-1139	2.9	13	
198	Growth Mechanism of Microcrystalline Silicon Prepared by Alternating Deposition of Amorphous Silicon and Hydrogen Radical Annealing. <i>Japanese Journal of Applied Physics</i> , 1992 , 31, L1388-L1391	1.4	13	
197	Design of Band Potential with a-SixGe1-x:H(F) Alloys. <i>Japanese Journal of Applied Physics</i> , 1987 , 26, L10	69 <u>-1.4</u> 72	2 13	
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194	Undoped and catalyst-free germanium nanowires for high-performance p-type enhancement-mode field-effect transistors. <i>Journal of Materials Chemistry C</i> , 2016 , 4, 5102-5108	7.1	12	
193	Atomic layer-by-layer epitaxy of oxide superconductors by MOCVD. <i>Applied Surface Science</i> , 1997 , 112, 30-37	6.7	12	
192	Photoluminescence Study of Self-Limiting Oxidation in Nanocrystalline Silicon Quantum Dots. <i>Materials Research Society Symposia Proceedings</i> , 2001 , 664, 2061		12	
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190	Self-limiting adsorption and in situ optical monitoring for atomic layer epitaxy of oxide superconductors layer epitaxy of oxide superconductors. <i>Thin Solid Films</i> , 1993 , 225, 284-287	2.2	12	
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188	Vidicon target of a p-i-n structure using a-Si:H. <i>Journal of Applied Physics</i> , 1980 , 51, 6422-6423	2.5	12	
187	Control of threshold voltage by gate metal electrode in molybdenum disulfide field-effect transistors. <i>Applied Physics Letters</i> , 2017 , 110, 133507	3.4	11	

186	Charge sensing and spin-related transport property of p-channel silicon quantum dots. <i>Japanese Journal of Applied Physics</i> , 2017 , 56, 04CK07	1.4	11
185	Germanium nanowires with 3-nm-diameter prepared by low temperature vapour-liquid-solid chemical vapour deposition. <i>Journal of Nanoscience and Nanotechnology</i> , 2011 , 11, 8163-8	1.3	11
184	Position-Controllable Ge Nanowires Growth on Patterned Au Catalyst Substrate. <i>Applied Physics Express</i> , 2009 , 2, 015004	2.4	11
183	Carrier transport by field enhanced thermal detrapping in Si nanocrystals thin films. <i>Journal of Applied Physics</i> , 2009 , 105, 124518	2.5	11
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180	Key capacitive parameters for designing single-electron transistor charge sensors. <i>Journal of Applied Physics</i> , 2012 , 111, 093715	2.5	11
179	Design Optimization of NEMS Switches for Suspended-Gate Single-Electron Transistor Applications. <i>IEEE Nanotechnology Magazine</i> , 2009 , 8, 174-184	2.6	11
178	Fabrication of Nanocrystalline Si by SiH4 Plasma Cell. <i>Materials Research Society Symposia Proceedings</i> , 1995 , 377, 51		11
177	Hole Transport in a-Si:H(F) Prepared by Hydrogen-Radical-Assisted Chemical Vapor Deposition. Japanese Journal of Applied Physics, 1986 , 25, 1783-1787	1.4	11
176	Fabrication of Nanostructure by Anisotropic Wet Etching of Silicon. <i>Japanese Journal of Applied Physics</i> , 1988 , 27, L1778-L1779	1.4	11
175	Back-action-induced excitation of electrons in a silicon quantum dot with a single-electron transistor charge sensor. <i>Applied Physics Letters</i> , 2015 , 106, 053119	3.4	10
174	GaAs/AlGaAs field-effect transistor for tunable terahertz detection and spectroscopy with built-in signal modulation. <i>Applied Physics Letters</i> , 2013 , 102, 122102	3.4	10
173	Demonstration of spin valve effects in silicon nanowires. <i>Journal of Applied Physics</i> , 2011 , 109, 07C508	2.5	10
172	Charge storage and electron/light emission properties of silicon nanocrystals. <i>Physica E: Low-Dimensional Systems and Nanostructures</i> , 2007 , 38, 59-63	3	10
171	Influence of the crystal orientation of substrate on low temperature synthesis of silicon nanowires from Si2H6. <i>Thin Solid Films</i> , 2008 , 517, 317-319	2.2	10
170	Bottom-up approach to silicon nanoelectronics. <i>Microelectronics Journal</i> , 2008 , 39, 171-176	1.8	10
169	Superconducting Properties of Ultrathin Films of \$bf YBa_{2}Cu_{3}O_{ninmbi{x}}\$ Prepared by Metalorganic Chemical Vapor Deposition at \$bf 500^{circ}C\$. Japanese Journal of Applied Physics, 1994, 33, L312-L314	1.4	10

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166	Methodology for Evaluating Operation Temperatures of Fin-Type Field-Effect Transistors Connected by Interconnect Wires. <i>Japanese Journal of Applied Physics</i> , 2013 , 52, 064203	1.4	9
165	Experimental Observation of Enhanced Electron Phonon Interaction in Suspended Si Double Quantum Dots. <i>Japanese Journal of Applied Physics</i> , 2010 , 49, 045203	1.4	9
164	Field-dependant hopping conduction in silicon nanocrystal films. <i>Journal of Applied Physics</i> , 2008 , 104, 123710	2.5	9
163	In SituOptical Monitoring of Two-Dimensional Crystal Growth in Layer-by-Layer Chemical Vapor Deposition of YBa2Cu3Ox. <i>Japanese Journal of Applied Physics</i> , 1993 , 32, L683-L686	1.4	9
162	Electrical properties of a CdTe/InSb hetero metal-insulator-semiconductor structure. <i>Applied Physics Letters</i> , 1988 , 52, 1306-1307	3.4	9
161	Low-voltage cathodoluminescence of ZnS single crystals. <i>Journal of Luminescence</i> , 1978 , 16, 323-330	3.8	9
160	Preparation of nanocrystalline silicon quantum dot structure by a digital plasma process. <i>Advances in Colloid and Interface Science</i> , 1997 , 71-72, 31-47	14.3	9
159	Fabrication and characterization of p-channel Si double quantum dots. <i>Applied Physics Letters</i> , 2014 , 105, 113110	3.4	8
158	Surface passivation of germanium nanowires using Al2O3and HfO2deposited via atomic layer deposition technique. <i>Japanese Journal of Applied Physics</i> , 2014 , 53, 06JG04	1.4	8
157	Scaling Analysis of Nanoelectromechanical Memory Devices. <i>Japanese Journal of Applied Physics</i> , 2010 , 49, 044304	1.4	8
156	Experimental evidence of increased deformation potential at MOS interface and its impact on characteristics of ETSOI FETs 2011 ,		8
155	Size Reduction and Phosphorus Doping of Silicon Nanocrystals Prepared by a Very High Frequency Plasma Deposition System. <i>Japanese Journal of Applied Physics</i> , 2011 , 50, 025002	1.4	8
154	Electron mobility enhancement in nanoscale silicon-on-insulator diffusion layers with high doping concentration of greater than 1 🛘 1018 cm 🖰 and silicon-on-insulator thickness of less than 10 nm. <i>Journal of Applied Physics</i> , 2011 , 110, 034502	2.5	8
153	Voltage-limitation-free analytical single-electron transistor model incorporating the effects of spin-degenerate discrete energy states. <i>Journal of Applied Physics</i> , 2008 , 103, 054508	2.5	8
152	Single-electron tunnelling via quantum dot cavities built on a silicon suspension nanobridge. <i>Microelectronic Engineering</i> , 2008 , 85, 1410-1412	2.5	8
151	New Design Concept and Fabrication Process for Three-Dimensional Silicon Photonic Crystal Structures. <i>Japanese Journal of Applied Physics</i> , 2007 , 46, 633-637	1.4	8

150	Operation of nanocrystalline-silicon-based few-electron memory devices in the light of electron storage, ejection, and lifetime characteristics. <i>IEEE Nanotechnology Magazine</i> , 2003 , 2, 88-92	2.6	8
149	Retardation in the Oxidation Rate of Nanocrystalline Silicon Quantum Dots. <i>Materials Research Society Symposia Proceedings</i> , 2000 , 638, 1		8
148	Carrier conduction in a Si-nanocrystal-based single-electron transistor-II. Effect of drain bias. Superlattices and Microstructures, 2000 , 28, 189-198	2.8	8
147	Reproducible Growth of Metalorganic Chemical Vapor Deposition Derived YBa2Cu3OxThin Films Using Ultrasonic Gas Concentration Analyzer. <i>Japanese Journal of Applied Physics</i> , 1999 , 38, 4727-4732	1.4	8
146	Generation of Electron Cyclotron Resonance Plasma in the VHF Band. <i>Japanese Journal of Applied Physics</i> , 1989 , 28, L1860-L1862	1.4	8
145	Photoluminescence of Nanocrystalline Silicon Quantum Dots with Various Sizes and Various Phosphorus Doping Concentrations Prepared by Very High Frequency Plasma. <i>Japanese Journal of Applied Physics</i> , 2012 , 51, 115202	1.4	8
144	Observation and coherent control of interface-induced electronic resonances in a field-effect[transistor. <i>Nature Materials</i> , 2017 , 16, 208-213	27	7
143	Growth of GeBi nanowire heterostructures via chemical vapor deposition. <i>Thin Solid Films</i> , 2011 , 519, 4174-4176	2.2	7
142	Study on Device Parameters of Carbon Nanotube Field Electron Transistors to Realize Steep Subthreshold Slope of Less than 60 mV/Decade. <i>Japanese Journal of Applied Physics</i> , 2011 , 50, 04DN01	1.4	7
141	Stochastic Coulomb blockade in coupled asymmetric silicon dots formed by pattern-dependent oxidation. <i>Applied Physics Letters</i> , 2008 , 92, 092110	3.4	7
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139	In situ real-time spectroscopic ellipsometry study of HfO2 thin films grown by using the pulsed-source metal-organic chemical-vapor deposition. <i>Journal of Applied Physics</i> , 2005 , 97, 023527	2.5	7
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137	Staircase-like structures in in situ optical reflectance measurement as an evidence for two-dimensional crystal growth in layer-by-layer chemical vapor deposition of YBa2Cu3Ox. <i>Applied Surface Science</i> , 1994 , 75, 259-262	6.7	7
136	Preparation and characterization of low-voltage cathodoluminescent ZnS. <i>Journal of Luminescence</i> , 1979 , 18-19, 365-368	3.8	7
135	Physically defined triple quantum dot systems in silicon on insulator. <i>Applied Physics Letters</i> , 2019 , 114, 073104	3.4	6
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